

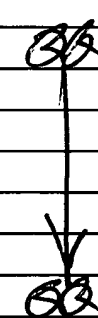

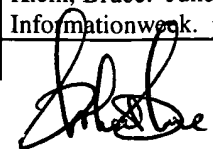
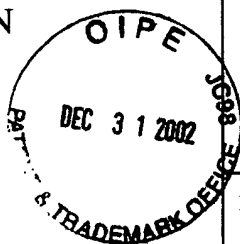


INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 005917 USA/FET/FET		SERIAL NO. 09/998,372	
				APPLICANT Young Joseph PAIK			
				FILING DATE November 30, 2001		GROUP 3723	
U.S. PATENT DOCUMENTS							
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						Yes	No
	WO 95/34866	12/21/95	WO	—	—	X	
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	WO 99/25520	05/27/99	WO	—	—	X	
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						Yes	No
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	WO 01/57823 A2	08/09/01	WO			X	
	EP 1 182 526 A2	02/27/02	Europe			X	
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